What is claimed is:

1. A substrate cleaning apparatus comprising:

a substrate support mechanism configured to support a substrate; and

a roll-type first cleaning member configured to clean a first surface of the substrate by rotating while being in contact with a bevel and/or an edge of the first surface of the substrate, wherein

a rotation axis of the first cleaning member is in parallel with the substrate, and

the first cleaning member comprises at least one large diameter portion and at least one small diameter portion.

2. The substrate cleaning apparatus according to claim 1, wherein

the substrate support mechanism is configured to hold the substrate and rotate the substrate.

3. The substrate cleaning apparatus according to claim 1, further comprising:

a roll-type second cleaning member facing the first cleaning member and configured to clean a second surface of the substrate by rotating while being in contact with a bevel and/or an edge of the second surface of the substrate, wherein

a rotation axis of the second cleaning member is in parallel with the substrate,

the second cleaning member comprises a large diameter

portion and a small diameter portion, and

the small diameter portion of the second cleaning member is located facing the large diameter portion of the first cleaning member, the large diameter portion of the second cleaning member is located facing the small diameter portion of the first cleaning member, and the first cleaning member and the second cleaning member rotate without being in contact with each other.

4. The substrate cleaning apparatus according to claim 3, wherein

each of the first cleaning member and the second cleaning member comprises a plurality of large diameter portions and a plurality of small diameter portions,

the large diameter portions and the small diameter portions are alternately arranged along longitudinal directions of the first cleaning member and the second cleaning member, thereby a plurality of grooves are formed in a circumferential direction,

each of the grooves are separated from the adjacent grooves by the large diameter portions and becomes independent shape.

5. The substrate cleaning apparatus according to claim 1, wherein

a rotation direction of the first cleaning member is a direction from a center of the substrate toward an edge of the substrate at a position where the first cleaning member is in contact with the substrate.

6. The substrate cleaning apparatus according to claim 1, further comprising:

a first nozzle configured to supply liquid to the first surface of the substrate in a direction toward an edge of the substrate.

7. The substrate cleaning apparatus according to claim 1, further comprising:

an actuator that swings the first cleaning member in a tangential direction, a radial direction, and/or a vertical direction of the substrate when the substrate is cleaned.

8. The substrate cleaning apparatus according to claim 1, wherein

the substrate has a polygonal shape, and

the substrate support mechanism moves the substrate in a direction along a side of the substrate and the first cleaning member comes into contact with a bevel and/or an edge along a side of the substrate.

9. The substrate cleaning apparatus according to claim 1, wherein

the substrate has a polygonal shape, and

the substrate cleaning apparatus further comprises a moving mechanism configured to move the first cleaning member in a direction along a side of the substrate.

10. A substrate cleaning member configured to clean a substrate, the substrate cleaning member comprising:

a first cleaning member configured to clean a first

surface of the substrate by rotating while being in contact with a bevel and/or an edge of the first surface of the substrate, the first cleaning member comprising a large diameter portion and a small diameter portion; and

a second cleaning member facing the first cleaning member and configured to clean a second surface of the substrate by rotating while being in contact with a bevel and/or an edge of the second surface of the substrate, the second cleaning member comprising at least one large diameter portion and at least one small diameter portion, wherein

rotation axes of the first cleaning member and the second cleaning member are in parallel with the substrate, and

the small diameter portion of the second cleaning member is located facing the large diameter portion of the first cleaning member, the large diameter portion of the second cleaning member is located facing the small diameter portion of the first cleaning member, and the first cleaning member and the second cleaning member are configured to rotate without being in contact with each other.

11. The substrate cleaning member according to claim 10, wherein

each of the first cleaning member and the second cleaning member comprises a plurality of large diameter portions and a plurality of small diameter portions,

the large diameter portions and the small diameter portions are alternately arranged along longitudinal directions of the first cleaning member and the second cleaning member, thereby a plurality of grooves are formed in a circumferential direction,

each of the grooves are separated from the adjacent grooves by the large diameter portions and becomes independent shape.